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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

re Patent Application of:

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Group Art Unit: 2823

Shunpei YAMAZAKI et al.)
Serial No. 09/436,984)

Filed: November 9, 1999

For: SEMICONDUCTOR DEVICE AND

MANUFACTURING METHOD THEREOF

CERTIFICATE OF MAILING

Examiner: William D. Coleman

AMENDMENT

Commissioner for Patents Washington, D.C. 20231

Sir:

hereby certify that this correspondence is being deposited with The United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231, or 12. 2. 202 a

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In response to the Office Action mailed July 31, 2002, please amend the above identified application as follows.

IN THE SPECIFICATION:

At page 1, line 1, please replace the title with a new title as follows:

-- SEMICONDUCTOR DEVICE HAVING AN IMPURITY GRADIENT IN THE IMPURITY REGIONS AND METHOD OF MANUFACTURE--

IN THE CLAIMS:

Please add the following new claims 56-59:

- 56. (New) The semiconductor device according to claim 32, wherein the pair of side walls overlap only the pair of first impurity regions.
- 57. (New) The semiconductor device according to claim 38, wherein the pair of side walls overlap only the pair of first impurity regions.
- 58. (New) The semiconductor device according to claim 44, wherein the pair of side walls overlap only the pair of first impurity regions.

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